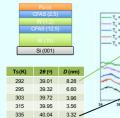




Low-Temperature Deposition

 $Co_2FeAl_{0.5}Si_{0.5}$ (CFAS)/W/CFAS trilayers were sputtered at substrate temperatures T_S :



Magnetic Properties

CFAS/W/CFAS trilayers : *

- Low Ts film has strong intergranular exchange coupling.
- This gives a highly square, low H_c loop. • Higher $T_s \rightarrow 50\%$ of the
- reversal is via domain rotation.
- The remainder is via nucleation and domain wall pinning.

Device Characterisation

- CFAS/Ag/CFAS nanopillars fabricated :
- Due to the lack of individual layer switching in multilayers using a W spacer, Ag was used.
- A 3 nm layer of Ag provided a loop with two distinct switches dependent on layer thickness.
- A small GMR of 0.025% was observed perpendicular-to-plane for device of (1×0.5) μm².
- Switching occurs at the same field as in the M-H loop, confirming layer thickness dependent switching.

 \rightarrow The is similar to CoFe and would be suitable for a GMR device.

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THE UNIVERSITY of York

[4] A. Hirohata et al., Materials, 11, 105 (2018)

Co,FeSia Alad

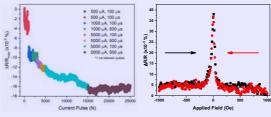
Roadmap on Heusler Alloys^[2]



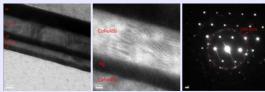
A. Hirohata et al., J. Magn. Magn. Mater. 509, 166711 (2020)
A. Hirohata et al., IEEE Trans. Magn. 51, 07160747 (2015)
J. Sagar et al., Appl. Phys. Lett. 105, 032401 (2014)

Current-Induced Crystallisation

CFAS/Ag/CFAS nanopillars :



High-resolution transmission electron micrographs :

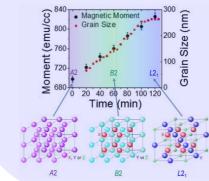


Cross-sectional TEM images of the GMR device with 300k and 800k magnification.

- Diffraction pattern confirms CFAS (220) crystallisation.
- Lattice constant is estimated to be 0.57 nm, which is 96.6% of that estimated by the corresponding XRD.

T CREST JEOL

Co2Fe(Al,Si) / Ag / Co2Fe(Al,Si) trilayers : *



The current-induced crystallisation leads to the reduction in the corresponding resistivity.

- This acts as memory potentiation for an artificial GMR synapse.
- This offers more realistic neuromorphic computation with higher efficiency.

Summarv

- The concept of the current-induced crystallisation has been successfully demonstrated in a Heusler-alloy GMR junction.
- Due to the nature of a simple electrical current introduction, a nanoelectronics device does not require an es but stores the operation cycle permane proc
- The current-induced crystallisation minimises any atomic diffusion and interfacial mixing to degrade their performance.

EPSRC

The current-induced crystallisation is expected to be used in a variety of nanoelectronics devices, including a neuromorphic node network.

eusler Alloy Films

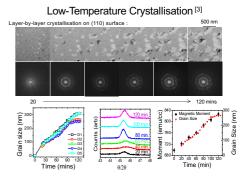
A. Hirohata¹

1000 % it ~2045

2029

2024

2019



Resistance change after a series of pulse current applications of 500 μA up to 5 mA for

100 μs up to 500 μs in a GMR device consisting of CFAS/Ag/CFAS.

The initial GMR effect is extremely small at only 0.04% and is very unstable, with no stable anti-parallel configuration.

 \bullet Using Ohm's law, the application of a 100 μA current for 10 s introduces 6.24×10^{-14} J to a Heusler alloy nanopillar (10 nm thick and 100

 $\,$ By assuming the resistivity is similar to that of Co (6.24 nW·m).

J/mol·K and the density of Co is 8.90 g/cm³.

For an ideal case, this increases the temperature of the Heusler layer by 51.5K.

Since the heat capacity of Co is 24.81

nm diameter).